

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10020047	12/07/2001	430	5	1756	ROSASCO

**APPLICANTS: Rothschild Mordechai; Liberman Vladimir;

**CONTINUING DATA VERIFIED:
THIS APPLN CLAIMS BENEFIT OF 60/317,694 09/06/2001

** FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	ATTORNEY DOCKET NO
35 USC 119 conditions met	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	M0635/7073
Verified and Acknowledged Examiners's initials <i>ER</i>		

TITLE : Attenuating phase shift mask for photolithography

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
		DRAWING	
		Sheet Draw.	Fig. Draw.
		Print Fig.	
ISSUE FEE		Application Examiner	
Amount Due	Date Paid		
		PREPARED FOR ISSUE	
<input type="checkbox"/> TERMINAL DISCLAIMER		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.	

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